

**REMARKS**

At the outset, the Examiner is thanked for the thorough review and consideration of the pending application. The office action dated April 12, 2004 has been received, and its contents carefully reviewed.

Claims 5-14 remain in the application with claims 5-9 and 10-14 amended and claims 1-4 withdrawn.

The Examiner rejected claims 11-14 under 35 U.S.C. § 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention; and claims 5-14 under 35 U.S.C. § 103(a) as being unpatentable over U.S. Patent No. 6,368,954 to Im (hereinafter "Im").

The rejection of claims 11-14 under U.S.C. § 112, second paragraph, is respectfully traversed and reconsideration is requested. Claim 11 has been amended, and Applicant respectfully requests the withdrawal of this rejection.

The rejection of claims 5-14 under U.S.C. § 103(a) is respectfully traversed and reconsideration is requested. Claim 5 is allowable over the cited references in that this claim recites a combination of elements including, for example, "stepping the mask by several micrometers using the mask stage" and "stepping the X-Y stage having the substrate to crystallize another block of the amorphous silicon film". Claim 11 is allowable over the cited references in that this claim recites a combination of elements including, for example, "stepping the mask by several micrometers so that the plurality of slits correspond to next portions of the amorphous silicon film that have not been crystallized" and "stepping the substrate to correspond to a next block of the amorphous silicon film, the next block having a portion with uncrystallized silicon film". Im does not teach or suggest at least these features of the claimed invention.

Im teaches a method where the mask and substrate move continuously relative to one another, rather than stepping from one position to another. (See col. 4, ll. 39-44; Abstract.) Further, while Im may teach moving either the masking system 150 or the sample stage 180, it does not teach a method where both are moved as part of the crystallization process. For example, Im does not disclose stepping the mask for minute movements, and then also stepping the X-Y stage to crystallize another block of the amorphous silicon. Im simply teaches that on


or the other could be used to move the mask and substrate relative to one another. Therefore, claims 5 and 11 and claims 5-10 and 12-14, which depend therefrom respectively, are allowable over Im.

If for any reason the Examiner finds the application other than in condition for allowance, the Examiner is requested to call the undersigned attorney at (202) 496-7500 to discuss the steps necessary for placing the application in condition for allowance. All correspondence should continue to be sent to the below-listed address.

If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time, or any other fees required to complete the filing of this response, may be charged to Deposit Account No. 50-0911. Please credit any overpayment to deposit Account No. 50-0911. A duplicate copy of this sheet is enclosed.

Dated: July 12, 2004

Respectfully submitted,

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